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PRE
AMEND A
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

priority Application Serial No. 08/984,730
priority Filing Date December 4, 1997
Inventor D.G. Custer et al.
Assignee Micron Technology, Inc.
priority Group Art Unit 3723
priority Examiner L. Wilson
Attorney's Docket No. MI22-1172
Title: Polishing Systems, Methods Of Polishing Substrates, and Methods Of Preparing
Liquids For Semiconductor Fabrication Processes

PRELIMINARY AMENDMENT

To: Assistant Commissioner for Patents
Washington, D.C. 20231

From: David G. Latwesen (Tel. 509-624-4276; Fax 509-838-3424)
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AMENDMENTS

In the Specification

At p. 1, before the "Technical Field" section, insert

RELATED PATENT DATA

This patent resulted from a divisional application of U.S. Patent
Application Serial No. 08/984,730, which was filed on December 4, 1997.

Amended Claims

Cancel claims 6-38.